



Abstract: We present the results of single event effects (SEE) testing and analysis investigating the effects of radiation on electronics. This paper is a summary of test results.

Introduction

NASA spacecraft are subjected to a harsh space environment that includes exposure to various types of ionizing radiation. The performance of electronic devices in a space radiation environment are often limited by their susceptibility to single-event effects (SEE). Ground-based testing is used to evaluate candidate spacecraft electronics to determine risk to spaceflight applications. Interpreting the results of radiation testing of complex devices is challenging. Given the rapidly changing nature of technology, radiation test data are most often application-specific and adequate understanding of the test conditions is critical [1].

Studies discussed herein were undertaken to establish the application-specific sensitivities of candidate spacecraft and emerging electronic devices to single-event upset (SEU), single-event latchup (SEL), single-event gate rupture (SEGR), single-event burnout (SEB), and single-event transient (SET).

For total ionizing dose (TID) results, see a companion paper submitted to the 2018 Institute of Electrical and Electronics Engineers (IEEE) Nuclear and Space Radiation Effects Conference (NSREC) Radiation Effects Data Workshop (REDW) entitled "NASA Goddard Space Flight Center's Compendium of Recent Total Ionizing Dose and Displacement Damage Dose Results" by A. D. Topper, *et al.* [2]

Test Techniques and Setup

A. Test Facilities

All tests were performed between February 2017 and February 2018. Heavy ion experiments were conducted at the Lawrence Berkeley National Laboratory (LBNL) 88-inch cyclotron [3], and at the Texas A&M University Cyclotron (TAMU) [4]. Both of these facilities provide a variety of ions over a range of energies for testing. Each device under test (DUT) was irradiated with heavy ions having linear energy transfer (LET) ranging from 0.07 to 86 MeV \cdot cm²/mg. Fluxes ranged from 1 \times 10² to 1 \times 10⁵ particles/cm²s, depending on device sensitivity. Representative ions used are listed in Tables I, and II. LETs in addition to the values listed were obtained by changing the angle of incidence of the ion beam with respect to the DUT, thus changing the path length of the ion through the DUT and the "effective LET" of the ion. Energies and LETs available varied slightly from one test date to another.

Proton SEE tests were performed at Massachusetts General Francis H. Burr Proton Therapy (MGH) [5], Tri-University Meson Facility (TRIUMF) [6], Northwestern Medicine Chicago Proton Center [7], California Protons Cancer Therapy Center (formerly Scripps Proton Therapy Center) [8], Mayo Clinic [9], ProVision Center for Proton Therapy [10], and the Proton Therapy Center at Cincinnati Children's Hospital [11].

Laser SEE tests were performed at the pulsed laser facility at the Naval Research Laboratory (NRL) [12], [13]. We tested with a pulsed laser at the Naval Research Laboratory using both Single-Photon Absorption (SPA) and Two-Photon Absorption (TPA) techniques [14] with the laser light having a wavelength of 590 nm resulting in a skin depth (depth at which the light intensity decreased to 1/e – or about 37% – of its intensity at the surface) of 2 μ m. A nominal pulse rate of 1 kHz was utilized. Pulse width was 1 ps, beam spot size ~1.2 μ m.

Table I: LBNL Test Heavy Ions

Ion	Energy (MeV)	Surface LET in Si (MeV \cdot cm ² /mg) (Normal Incidence)	Range in Si (μ m)
LBNL 10 MeV per amu time			
¹⁸ O	183	2.2	226
²² Ne	216	3.5	175
⁴⁰ Ar	400	9.7	130
²⁸ V	508	14.6	113
⁶² Ni	680	21.2	108
⁸⁴ Kr	906	30.2	113
¹⁰⁷ Ag	1039	48.2	90
¹²⁴ Xe	1233	58.8	90

Table II: TAMU Test Heavy Ions

Ion	Energy (MeV)	Surface LET in Si (MeV \cdot cm ² /mg) (Normal Incidence)	Range in Si (μ m)
TAMU 15 MeV per amu time			
⁴ He	210	1.3	428
²⁰ Ne	300	2.5	316
⁴⁰ Ar	599	7.7	229
⁶³ Cu	944	17.8	172
¹⁶³ La	1259	25.4	170
¹⁹⁶ Ag	1634	35.5	156
¹⁹⁷ La	1734	47.3	156
¹⁹⁷ La	2954	80.2	155
TAMU 25 MeV per amu time			
⁸⁴ Kr	2081	19.8	332
¹³⁶ Xe	3197	38.9	286

amu = atomic mass unit

B. Test Method

Unless otherwise noted, all tests were performed at room temperature and with nominal power supply voltages. We recognize that high-temperature and worst-case power supply conditions are recommended for SEL device qualification. Unless otherwise noted, SEE testing was performed in accordance with JEDEC JESD57A test procedures [15].

1) SEE Testing - Heavy Ion:

Depending on the DUT and the test objectives, one or more of three SEE test methods were typically used:

Dynamic – The DUT was exercised and monitored continuously while being irradiated. The type of input stimulus and output data capture methods are highly device- and application-dependent. Generally, analog devices were provided with a time-varying signal while an oscilloscope captured variations in output waveforms (e.g. a function generator providing a pair of square wave inputs to a comparator while an oscilloscope captured output glitches). Digital devices were operated by a computer, FPGA, or microcontroller while outputs were monitored with the same (e.g. a memory actively written-to or read-from by an FPGA), or with an oscilloscope or logic analyzer as appropriate (e.g. a data-converter with analog output channels). Occasionally a golden-chip test may be performed where an irradiated device is directly compared to an identical, unirradiated device and any differences recorded. In all cases the power supply levels were actively monitored during irradiation. These results are highly application-dependent and may only represent the specific operational mode tested.

Static/Biased – The DUT was provided basic power and configuration information (where applicable), but not actively operated during irradiation. The device output may or may not have been actively monitored during irradiation, while the power supply current was actively monitored for changes.

Unpowered – The DUT was characterized prior-to and immediately following irradiation, but was completely unpowered and unmonitored during irradiation.

In SEE experiments, DUTs were monitored for soft errors, such as SEUs, and for hard errors, such as SEGR. Detailed descriptions of the types of errors observed are noted in the individual test reports [16], [17]. SET testing was performed using high-speed oscilloscopes controlled via National Instruments LabVIEW®. [19]. Individual criteria for SETs are specific to the device and application being tested. Please see the individual test reports for details [16], [17].

Heavy ion SEE sensitivity experiments include measurement of the linear energy transfer threshold (LET_{th}) and cross section at the maximum measured LET. The LET_{th} is defined as the maximum LET value at which no effect was observed at an effective fluence of 1 \times 10¹⁰ particles/cm². In the case where SEB threshold measurements are made of the SEGR or SEB threshold V_{th} (drain-to-source voltage) as a function of LET and ion energy at a fixed V_{gs} (gate-to-source voltage).

2) SEE Testing - Proton:

Proton SEE tests were performed in a manner similar to heavy ion exposures. However, because protons usually cause SEE via indirect ionization of recoil particles, results are parameterized in terms of proton energy rather than LET. Because such proton-induced nuclear interactions are rare, proton tests also feature higher cumulative fluences and particle flux rates than heavy ion experiments.

3) SEE Testing - Pulsed Laser Facility Testing:

The DUT was mounted on an X-Y-Z stage in front of a 100 mm lens that produces a spot diameter of approximately 1 μ m at full-width-half-maximum (FWHM). The X-Y-Z stage can be moved in steps of 0.1 μ m for accurate determination of SEE-sensitive regions in front of the focused beam. An illuminator, together with a charge-coupled device (CCD) camera and monitor, were used to image the area of interest thereby facilitating accurate positioning of the device in the beam. The pulse energy was varied in a continuous manner using a polarizer/half-waveplate combination and the energy was monitored by splitting off a portion of the beam and directing it at a calibrated energy meter.

Table V: Summary of SEE Test Results

Part Number	Manufacturer	LDC or Wafer, (REAG ID#)	Device Function	Technology	Particle: (Facility/Year/ Month) P.I.	Test Results: LET in MeV \cdot cm ² /mg, σ in cm ² /device, unless otherwise specified	Supply Voltage	Sample Size (Number Tested)
Memory Devices:								
AS008MA12A	Avalanche Technology	5216 (17-011)	Non-Volatile Memory	CMOS, MRAM	H: (TAMU2017Mar) DC: (TAMU2017Oct) TW	SEL LET _{th} > 85.4; SEU LET _{th} > 120.7; SEFI LET _{th} < 1.84; SEFI σ 3.2 \times 10 ⁻¹⁰ cm ² [19]	1.8 and 2.0 V	2
MT46V128MP	Micron	0830 (16-019), 1012 (16-020)	DDR SDRAM	CMOS	H: (TAMU2017June) MJC	SEL LET _{th} > 34.9; SEFI LET _{th} < 1.3; SEFI σ ~ 5 \times 10 ⁻⁴ cm ² [20]	2.5 V	2
MT29F128G08AJAAW-P-ITZ	Micron	1504 (16-013)	Flash	CMOS	H: (TAMU 2017Mar) MJC	Page Program Failure LET < 3.5	3.3 V	5
MT29F4G08ABADAWP-IT-D	Micron	1644 (17-012 or 17-040)	Flash	CMOS	H: (TAMU2017Mar) MJC	SEU LET _{th} < 2.8; SEU σ ~ 2 \times 10 ⁻¹⁰ cm ² /bit; SEFI LET _{th} < 2.8; SEFI σ ~ 5 \times 10 ⁻⁵ cm ² ; SEU LET _{th} < 0.89; SEU σ (MLC mode) ~ 1.8 \times 10 ⁻¹¹ cm ² /bit; SEU σ (SLC mode) ~ 9 \times 10 ⁻¹¹ cm ² /bit; SEFI LET _{th} < 0.89; SEFI σ ~ 2 \times 10 ⁻⁴ cm ² ; SEL LET _{th} > 58.78 [21]	3.3 V	3
MT29F1T08CMHBBJ4	Micron	(17-049)	Flash	CMOS	H: (TAMU2017June, LBNL2017June) TW	SEU LET _{th} < 0.89; SEU σ ~ 1.6 \times 10 ⁻¹⁰ cm ² /bit; SEFI LET _{th} ~ 1.78 < x < 3.49; SEFI σ ~ 1 \times 10 ⁻¹⁰ cm ² ; 200 MeV protons, SEFI σ ~ 6.93 \times 10 ⁻¹⁰ cm ² ; Upset mode has elevated current draw. [22]	3.3 V	6
MT29F512G08ACUBBH8	Micron	(17-051)	Flash	CMOS	H: (LBNL2017June) MJC	SEU LET _{th} < 0.89; SEU σ ~ 1.6 \times 10 ⁻¹⁰ cm ² /bit; SEFI LET _{th} ~ 1.78 < x < 3.49; SEFI σ ~ 1 \times 10 ⁻¹⁰ cm ² ; 200 MeV protons, SEFI σ ~ 6.93 \times 10 ⁻¹⁰ cm ² ; Upset mode has elevated current draw. [22]	3.3 V	3
MEMPEK1W016GAXT	Intel	(17-045)	Non-Volatile Memory	CMOS/PCM	Protons: (Chicago2017Nov) EW/TW		12 V	4

Power Transistors:								
BSS84KAV	NXP Semiconductor	(16-024)	MOSFET	p-channel trench	H: (TAMU2017Mar; LBNL2017Apr) JML/MCC	886 MeV Kr (LET=31) part-part variability with SEGR at ~46 V _{DS} . No failures with 659 MeV Cu (LET=21) at full rated ~50 V _{DS} . 886 MeV Kr (LET=31) part-part variability with SEGR at ~150 V _{DS} . No failures with 659 MeV Cu (LET=21) at full rated ~50 V _{DS} . [23]	0 V _{DS}	6
SQJ431EP-TI-GE3	Vishay	(16-025)	MOSFET	p-channel trench	H: (LBNL2017Apr) JML/MCC	886 MeV Kr (LET=31) part-part variability with SEGR at ~150 V _{DS} . No failures with 659 MeV Cu (LET=21) at full rated ~50 V _{DS} . [23]	0 V _{DS}	4
Si7414DN-TI-E3	Vishay	(16-030)	MOSFET	n-channel trench	H: (TAMU2017Mar; LBNL2017Apr) JML/MCC	886 MeV Kr (LET=31) part-part variability with SEGR at ~150 V _{DS} . No failures with 659 MeV Cu (LET=21) at full rated ~50 V _{DS} . [23]	0 V _{DS}	11
SQS460EN-TI-GE3	Vishay	(17-005)	MOSFET	n-channel trench	H: (TAMU2017Mar; LBNL2017Apr) JML/MCC	886 MeV Kr (LET=31) part-part variability with SEGR at ~150 V _{DS} . No failures with 659 MeV Cu (LET=21) at full rated ~50 V _{DS} . [23]	0 V _{DS}	21
NVTF55116PLWFTAG	ON Semiconductor	(17-006)	MOSFET	p-channel	H: (TAMU2017Mar; LBNL2017Apr) JML/MCC	886 MeV Kr (LET=31) part-part variability with SEGR at ~150 V _{DS} . No failures with 659 MeV Cu (LET=21) at full rated ~50 V _{DS} . [23]	0 V _{DS}	6
CGHV5930F	CREE	C32956S, C32956S, D1312S (17-065)	JFET	GaN HEMT	H: (TAMU2017Jun; 2017Oct) JML	Static and RF-mode tests reveal significant part-part variability; additional testing scheduled. Contact PI.	Static: ~5 V _{DS} ; RF: 50 V _{DS}	7
Engineering Samples, various	GE	(17-084)	MOSFET	SIC VDMOS	H: (TAMU2017Jun) JML	Contact PI.	0 V _{DS}	84

FPGA Devices:								
RT4G150-CB1657PROTO	Microsemi	1638 (17-003)	FPGA	65 nm CMOS	H: (TAMU2017Mar) MB	Flip-Flops: <8Seu LET _{th} <1.8 Configuration: SEU LET _{th} > 80 SEL LET _{th} > 60 [24]	nominal	1
XCKU040-1LFFVA1156I Kintex-UltraScale	Xilinx	1509 (15-061)	FPGA	FPGA (20 nm planar)	H: (TAMU2017Mar; TAMU2017Dec) MB	Configuration bits: SEU LET _{th} <0.07; SEFI LET _{th} <1.8 SEL LET _{th} > 50 [25]	nominal (1 each date)	2

Miscellaneous Devices:								
02G-P4-6152-KR	nVidia	2016 (17-039)	Processor	14 nm FinFET CMOS	Protons: (MGH2017Apr) EW	200 MeV protons, SEFI σ ~ 1.42 \times 10 ⁻¹⁰ cm ² ; SEU σ ~ 1.37 \times 10 ⁻¹⁰ cm ² . Upset modes include SEFI, pixel artifacts and clock trace failure. [26]	12 VDC	1
Engineering Samples	NASA GRC	(17-066)	Ring Oscillator	SIC	H: (TAMU2017Oct) JML	no catastrophic SEE up to 2006 MeV Au (LET=1768); SEL LET _{th} > 79; SET LET _{th} < 13; SET σ ~ 5 \times 10 ⁻³ cm ² Observed SETs included: 1) Changes in the pulse-width on the output, both shortening and lengthening of the duty cycle, 2) False triggers on the thermal shutdown flag, and 3) Altering of the 24kHz output frequency for no more than one clock cycle. [27]	+/- 28 V	3
DRV102	Texas Instruments	1440 (16-037)	PWM Solenoid/ Valve Drive	CMOS	H: (TAMU2017Jun) MJC	SEU LET _{th} < 2.8; SEU σ ~ 2 \times 10 ⁻¹⁰ cm ² /bit; SEFI LET _{th} < 2.8; SEFI σ ~ 5 \times 10 ⁻⁵ cm ² ; SEU LET _{th} < 0.89; SEU σ (MLC mode) ~ 1.8 \times 10 ⁻¹¹ cm ² /bit; SEU σ (SLC mode) ~ 9 \times 10 ⁻¹¹ cm ² /bit; SEFI LET _{th} < 0.89; SEFI σ ~ 2 \times 10 ⁻⁴ cm ² ; SEL LET _{th} > 58.78 [21]	28 V	6
AD654	Analog Devices	0630 (16-036)	Op-Amp	Bipolar	H: (LBNL2017Apr) MJC	SEL LET _{th} > 58.78; LET _{th} < SET 2.19 [28]	1 and 5 V	4
KSW-2-46+	MiniCircuits	(17-004)	RF Switch	CMOS	Laser: (NRL2017Feb) MCC	No destructive events observed at a laser energy of ~64 nJ. Worst case transients had an amplitude of approximately 1 V and a duration of 10 ns.	-5 V	2
TPS7A4501	Texas Instruments	1639AA (17-062)	Low Dropout Voltage Regulator	Bipolar	H: (TAMU2017Oct) MJC	No destructive events observed for Au ion LET = 87	6.3 V	3

Part Number	Manufacturer	(REAG ID#)	Device Function	Technology	Particle: (Facility/Year/ Month) P.I.	Test Results: LET in MeV/cm ² ; σ in cm ² /device, unless otherwise specified	Supply Voltage	Sample Size (Number Tested)
Diodes:								
BAS70-05-7-F	Diodes, Inc.	(16-026)	Diode	Schottky	H: (LBNL2017Apr) MCC	No failures or degradation observed at 100% of reverse voltage when irradiated up to 1232 MeV Xe (LET = 58.8). Degradation was observed during beam run when biased at 100% of reverse voltage and irradiated with 1232 MeV Xe (LET = 58.8), but all post-irradiation electrical parameter measurements remained within specification.	70 V	3
NSR0140P275G	ON Semiconductor	(16-028)	Diode	Schottky	H: (LBNL2017Apr) MCC	Degradation was observed during beam run when biased at 100% of reverse voltage and irradiated with 1232 MeV Xe (LET = 58.8), but all post-irradiation electrical parameter measurements remained within specification.	40 V	3
1N5711	Semicoa	(17-064)	Diode	Schottky	H: (LBNL2017Apr) MCC	Degradation was observed during beam run when biased at 100% of reverse voltage and irradiated with 1232 MeV Xe (LET = 58.8), but all post-irradiation electrical parameter measurements remained within specification.	70 V	4
CMPD2003 TR	Central Semiconductor	(17-015)	Diode	Switching	H: (LBNL2017Apr) MCC	No failures or degradation observed at 100% of reverse voltage when irradiated up to 1232 MeV Xe (LET = 58.8).	200 V	3
MMBD1501A	Fairchild Semiconductor	(17-016)	Diode	Switching	H: (LBNL2017Apr) MCC	No failures or degradation observed at 100% of reverse voltage when irradiated up to 1232 MeV Xe (LET = 58.8).	200 V	3
BAS21-215	NXP Semiconductor	(17-017)	Diode	Switching	H: (LBNL2017Apr) MCC	No failures or degradation observed at 100% of reverse voltage when irradiated up to 1232 MeV Xe (LET = 58.8).	200	3
BAS20LT1G	ON Semiconductor	(17-018)	Diode	Switching	H: (LBNL2017Apr) MCC	No failures or degradation observed at 100% of reverse voltage when irradiated up to 1232 MeV Xe (LET = 58.8).	200	3
BAS21-E3-08	Vishay	(17-019)	Diode	Switching	H: (LBNL2017Apr) MCC	No failures or degradation observed at 100% of reverse voltage when irradiated up to 1232 MeV Xe (LET = 58.8).	200	3